

## Main Unit Spec

Model Type	i-Line (365 nm) Stepper
Wafer Size	300 mm
Resolution	≤ 0.35 μm
Numerical Aperture (NA)	0.45 ~ 0.57
Reticle Size	6 in. (0.25 in. thick)
Reduction Ratio	4:1
Field Size	26 mm (max) x 33 mm (max)
Overlay Accuracy	SMO <sup>1</sup> ≤ 15 nm ( m  + 3σ) MMO <sup>1</sup> ≤ 20 nm ( m  + 3σ)
Footprint (W x D x H)	2,300 mm × 3,660 mm × 3,000 mm
Options	<sup>1</sup> Overlay Accuracy Improvement Option Productivity Improvement Option Non-linear Overlay Compensation (EAGA-FL) Low Oxygen Exposure (LOX) Pellicle Particle Checker Chemical Filtering Resist Outgassing Unit PC Remote Console Online Functions (GEM)